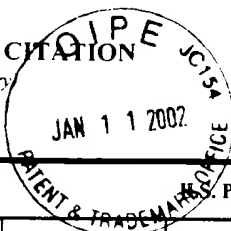


INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)



Docket Number (Optional)

P-6124

Application Number

09/833.363

Applicant(s)

Boieriu et al.

Filing Date

04/12/2001

Group Art Unit

2878

PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
SL		5,410,168	04/25/95	Hisa	—	—	

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FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
SL		JP 63-046765	12/20/94 4/98	JAPAN	—	—	als	
SL		JP 2-272766	11/7/90	JAPAN	—	—	als	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

SL		W. Kern and D.A. Puotinen, Cleaning solution based on hydrogen peroxide for use in silicon semiconductor technology, RCA Rev. 31, pp. 187-206 (1970)

EXAMINER

SL Lee

DATE CONSIDERED

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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.